

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Vernon et al. Art Unit : Unknown
Serial No. : Examiner : Unknown
Filed : March 26, 2004 Assignee : Intel Corporation
Title : CONTINUOUS SLOPED PHASE EDGE ARCHITECTURE FABRICATION
TECHNIQUE USING ELECTRON OR OPTICAL BEAM BLUR FOR SINGLE
PHASE SHIFT MASK RET

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Applicants submit the references listed on the attached form PTO-1449.

This statement is being filed with the application. A copy of the listed U.S. document is not provided in accordance with the waiver posted on the U.S. Patent Office website. Accordingly, only copies of non-patent literature are enclosed.

Consideration of the foregoing and enclosures plus the return of a copy of the enclosed form PTO-1449 with the Examiner's initials in the left column per MPEP 609 are earnestly solicited along with an early action on the merits.

Please apply any charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,



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Date: March 26, 2004

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March 26, 2004

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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-920001	Application No.
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Vernon et al.	
		Filing Date March 26, 2004	Group Art Unit

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	6,436,590 B2	8/20/2002	Wang et al.			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents or Published Foreign Patent Applications							
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation
							Yes No
	AL						
	AM						
	AN						
	AO						
	AP						

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AQ	Wang et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design", Proceedings of the SPIE; The International Society for Optical Engineering Conference; vol. 4562; pgs. 406-417, 2002.
	AR	Pfau et al., "Gradient Phase-Shifter Transitions Fabricated by Ion Milling", SPIE, Vol. 1674 Optical/Laser Microlithography V, pgs. 585-593, 1992.
	AS	
	AT	

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	